

A. Interconnect & Package 분과

Room H

하нас퀘어 (B115)

일 시 : 2월 17일(금) 13:40-15:10

세션명 : [FH3-A] 디스플레이용 배선 및 TCO

좌 장 : 손현철(연세대학교)

FH3-A-1 13:40-14:10 **[Invited]**TFT Fabrication by using Soluble Oxide Semiconductor and Gate Insulator

저자: 김정한, 김치완, 김철홍, 채기성, 전명철

소속: LG 디스플레이 R&D 센터

FH3-A-2 14:10-14:25 Effect of Metal Electrode and Annealing Process on the Electrical Performance of Amorphous In-Ga-Zn-O Thin Film Transistor

저자: 이영주¹, 임정열¹, 정성엽¹, 연한울¹, 권장연¹, 이제훈², 주영창¹

소속: ¹Department of Materials Science & Engineering, Seoul National University, ²Samsung Electronics Co., Ltd.

FH3-A-3 14:25-14:40 Ga doped ZnO (GZO) by Atomic Layer Deposition for Transparent Conducting Oxides

저자: Taewook Nam, Won-Seon Lee, and Hyungjun Kim

소속: Yonsei University

FH3-A-4 14:40-15:10 **[Invited]**Transparent Conducting Oxide Thin Films Deposited by Atomic Layer Deposition

저자: Jin-Seong Park

소속: Department of Materials Science and Engineering, Dankook University